



MICRONIX™

EDI

Ultrapure Water Technologies

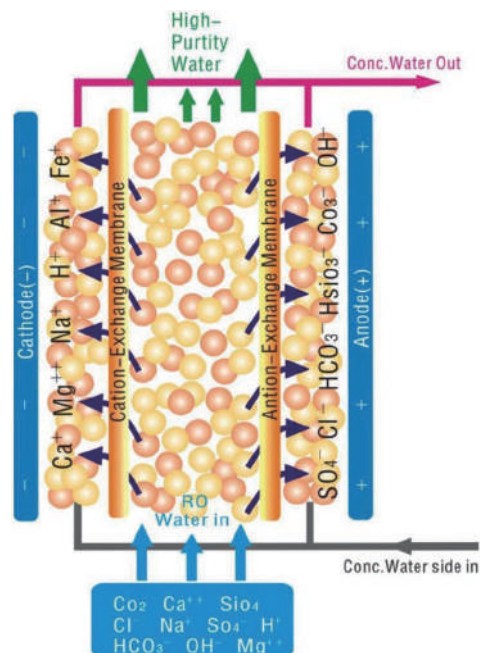


RELIABLE TECHNOLOGY for ULTRAPURE WATER PRODUCTION

EDI, electrodeionisation, uses electrical current to ionize molecules and separate dissolved ions from RO permeate.

Based on our references all over Asia in the water treatment business, we have presented solutions to the industries that need highest-purity water: semiconductor industry, LED industry, electronics industry, power plants, and many other different applications.

EDI technology eliminates the needs to regenerate chemicals and the services to exchange tanks. It is a simple and eco-green method to produce consistent ultrapure water with resistivity up to 18MΩ, which create a milestone in water treatment industry.



ADVANTAGES of MICRONIX EDI TECHNOLOGY

Stable performance and quality ultrapure water

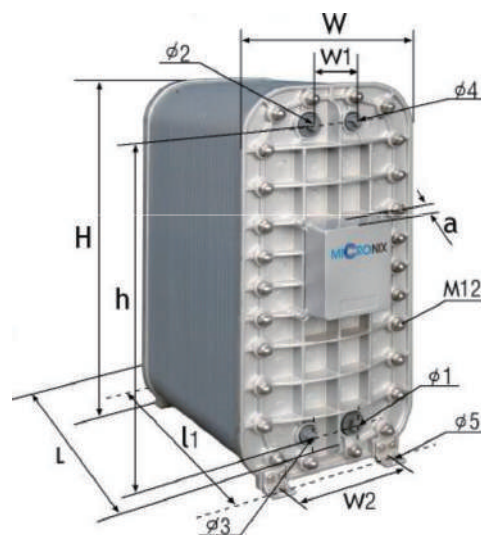
- Reliable product water with high resistivity up to 18MΩ · cm
- Wide range of water flow options satisfy different demands

More resin capacity

- The extended module's height creates larger space for resin capacity
- Enlarger polishing area to ensure the quality of the product water

Low power consumption

- Patented power-saving design lowers power consumption
- 30% power consumption of the competitor's stack

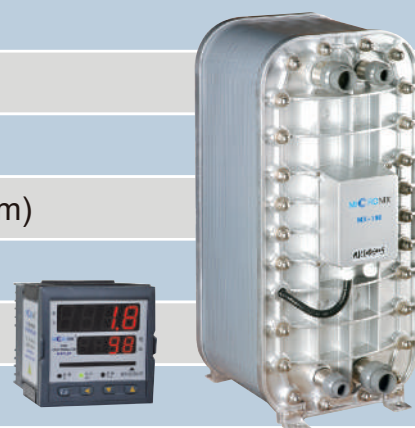


MODULE DIMENSION

Model	L	W	H	h	l1	w1	w2	Ø1	Ø2	Ø3	Ø4	Ø5	M	a
MX-25	260	310	680	535	135	80	200	DN25 (1")	DN25 (1")	DN15 (1/2")	DN15 (1/2")	10.5x20	M12	50
MX-50	310	310	680	535	188	80	200							
MX-100	439	310	680	535	280	80	200							
MX-200	580	310	680	535	465	80	200							
MX-300	705	310	680	535	585	80	200							
MX-500	910	310	680	535	790	80	200							
MX-650	910	310	680	535	790	80	200	DN40	DN40	DN25	DN25			

OPERATING FEEDWATER CONDITION

Feedwater Source	2 pass RO water
Conductivity Equivalent	$\leq 20 \mu\text{S/cm}$
pH	7.5 to 9
Total Hardness	$< 1.0\text{ppm}$ (recommendation: $< 0.5\text{ppm}$)
Total CO ₂	$< 3.0\text{ppm}$
Temperature	5°C to 38°C
Inlet Water Pressure	0.15 to 0.45 MPa
Particles	$< 1 \mu\text{m}$
Organics	TOC $< 0.5\text{ppm}$ (Undetectable recommended)
Oxidizers	Cl ₂ $< 0.05\text{ppm}$; O ₃ $< 0.02\text{ppm}$ (Undetectable recommended)
Metals	Fe, Mn, and transition metals $< 0.01\text{ppm}$
Silica	$< 0.5\text{ppm}$ (as SiO ₂)



EDI MODULE SPECIFICATION

Model	MX-650	MX-500	MX-300	MX-200	MX-100	MX-50	MX-25
Resin for Concentrate Chamber	Yes	Yes	Yes	Yes	Yes	Yes	Yes
Operating Voltage (DCV)	90-170	90-170	90-170	50-150	20-120	15-60	8-40
Design Voltage (DCV)	0-330	0-330	0-330	0-330	0-330	0-220	0-220
Operating Current (DCA)	≤ 3.5	≤ 3.5	≤ 3.5	≤ 3.5	≤ 3.5	≤ 3.5	≤ 3.5
Design Current (DCA)	6	6	6	6	6	6	6
Product Flow Range (m ³ /h)	5.5-7.5	4-6	2.5-4.4	1.5-2.4	0.8-1.4	0.3~0.75	0.15-0.3
Max. Product Flow (m ³ /h)	7.5	6	4.4	2.4	1.4	0.75	0.3
Recovery Rate (%)	90-95	90-95	90-95	90-95	90-95	80-95	75-85
Product Resistivity (MΩ·cm)	15-18	15-18	15-18	15-18	15-18	15-18	15-18
Feed Pressure (MPa)	0.15-0.45	0.15-0.45	0.15-0.45	0.15-0.45	0.15-0.45	0.15-0.45	0.15-0.45
Max. Pressure (MPa)	0.55	0.55	0.55	0.55	0.55	0.55	0.55
Feed / Product Water Piping	DN40	DN25	DN25	DN25	DN25	DN25	DN25
Inlet / Outlet Concentrate Piping	DN25	DN15	DN15	DN15	DN15	DN15	DN15

EDI SYSTEM REFERENCE

The generated high purity deionized product water can be used in the industries that need ultrapure water with resistivity up to $18\text{M}\Omega$, including semiconductor industry, electronic industry, power plant ... etc.

Semiconductor Industry - Product Water: $100\text{ m}^3/\text{h} \geq 16\text{M}\Omega\cdot\text{cm}$



Semiconductor Industry - Product Water: $600\text{ m}^3/\text{h} \geq 16\text{M}\Omega\cdot\text{cm}$



Power Plant - Product Water: $3 \times 108\text{ m}^3/\text{h}$



Please contact for more information